

Notice of References Cited	Application/Control No. 09/921,555	Applicant(s)/Patent Under Reexamination UEDA ET AL.	
	Examiner Michael Kornakov	Art Unit 1746	Page 1 of 1

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-			
	B	US-			
	C	US-			
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FOREIGN PATENT DOCUMENTS

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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Handbook of semiconductor wafer cleaning technology. Edited by W.Kern, 1993 by Noyes Publications, pages 3, 137-141
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	X	Menon, V.B. and Donovan, R.P. Microcontamination, 8(11):29-34

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.